U.S. Depart	tment of	Commerce, Patent	and Trademark	Atty. Docket No.			Application No.		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT OIPE				TNCR.178ÜS1			10/613,634		
				Applicant(s)			Conf. No.		
(Use several sheets if necessary)				Wayne Chen et al.	Wayne Chen et al.			4612	
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				July 3, 2003			2877		
2			U.S. Pa	atent Documents					
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			Foreign	Patent Documents		.			
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		Document	Date	Country	Class	Subclass	Yes	No	
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through									